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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/807,303	03/24/2004	Yukihiro Ushiku	04329.2459-01	3815
22852	7590 10/21/2004		EXAMINER	
FINNEGAN LLP	, HENDERSON, FAF	MENZ, DOUGLAS M		
1300 I STREE	ET, NW	ART UNIT	PAPER NUMBER	
WASHINGTON, DC 20005			2824	

DATE MAILED: 10/21/2004

Please find below and/or attached an Office communication concerning this application or proceeding.

Office Action Summary		Application No.	Applicant(s)				
		10/807,303	USHIKU, YUKIHIRO				
		Examiner	Art Unit				
		Douglas M Menz	2824	AN			
Period for A SH THE - Exte after - If the - If NO - Failu Any	ORTENED STATUTORY PERIOD FOR REPLY MAILING DATE OF THIS COMMUNICATION. nsions of time may be available under the provisions of 37 CFR 1.13 SIX (6) MONTHS from the mailing date of this communication. Period for reply specified above is less than thirty (30) days, a reply operiod for reply is specified above, the maximum statutory period were to reply within the set or extended period for reply will, by statute, reply received by the Office later than three months after the mailing ed patent term adjustment. See 37 CFR 1.704(b). Responsive to communication(s) filed on 24 M	Y IS SET TO EXPIRE 3 MONTH(36(a). In no event, however, may a reply be time of within the statutory minimum of thirty (30) days will apply and will expire SIX (6) MONTHS from the cause the application to become ABANDONE of date of this communication, even if timely filed alarch 2004.	(S) FROM nely filed s will be considered timely, the mailing date of this cor D (35 U.S.C. § 133).				
3)	, _						
Disposit	ion of Claims						
5)□ 6)⊠ 7)□	4) Claim(s) 9-16 is/are pending in the application. 4a) Of the above claim(s) is/are withdrawn from consideration. 5) Claim(s) is/are allowed. 6) Claim(s) 9-16 is/are rejected. 7) Claim(s) is/are objected to. 8) Claim(s) are subject to restriction and/or election requirement.						
Applicati	ion Papers						
10)⊠	The specification is objected to by the Examine The drawing(s) filed on 24 March 2004 is/are: Applicant may not request that any objection to the Replacement drawing sheet(s) including the correct The oath or declaration is objected to by the Ex	a)⊠ accepted or b)□ objected to drawing(s) be held in abeyance. See ion is required if the drawing(s) is obj	e 37 CFR 1.85(a). jected to. See 37 CFI	R 1.121(d).			
Priority u	under 35 U.S.C. § 119						
a)l	Acknowledgment is made of a claim for foreign All b) Some * c) None of: 1. Certified copies of the priority documents 2. Certified copies of the priority documents 3. Copies of the certified copies of the priority application from the International Bureau See the attached detailed Office action for a list	s have been received. s have been received in Applicati rity documents have been receive u (PCT Rule 17.2(a)).	on No ed in this National S	Stage			
2) 🔲 Notic 3) 🔯 Inforr	e of References Cited (PTO-892) e of Draftsperson's Patent Drawing Review (PTO-948) mation Disclosure Statement(s) (PTO-1449 or PTO/SB/08) r No(s)/Mail Date 3/24/04.	4) ☐ Interview Summary Paper No(s)/Mail Da 5) ☐ Notice of Informal P 6) ☑ Other: <u>Search Histo</u>	ate atent Application (PTO-	-152)			

Application/Control Number: 10/807,303

Art Unit: 2824

DETAILED ACTION

Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.

Claims 9-16 are rejected under 35 U.S.C. 102(e) as being anticipated by Kobayashi (US 5909626).

Regarding claim 9, Kobayashi discloses a semiconductor device comprising:

A semiconductor substrate (4) having a first region and a second region (Fig. 4E);

A buried insulating film (3) formed in the first region of the semiconductor substrate (Fig. 4E);

At least one first single crystalline semiconductor layer (9) having a semiconductor element formed therein and formed on the buried insulating film;

At least one second single crystalline semiconductor layer formed in the second region and in contact with the semiconductor substrate (*Vertical-type power element forming region*, Fig. 4E); and

Application/Control Number: 10/807,303

Art Unit: 2824

An element isolation region (20) for isolating the single crystalline semiconductor layers from each other,

Wherein all the element isolation insulating films in the element isolation region (20) have the same height from the semiconductor substrate (Fig. 4E and Col. 7).

Regarding claim 10, Kobayashi further discloses wherein the first single crystalline semiconductor layer formed in the first region consists of a plurality of semiconductor layers (9,13) having a plurality of film thicknessess (Fig. 4E and Col. 7).

Regarding claims 11-12, Kobayashi further discloses wherein a CMOS element is formed in the first region and a bipolar element is formed in the second region (vertical-type power element forming region, Fig. 4E).

Regarding claims 13-16, Kobayashi further discloses wherein a MOS transistor is formed in a predetermined first single crystalline semiconductor layer of the first region; a bipolar transistor is formed in a predetermined second single crystalline semiconductor of the second region (*vertical-type power element forming region*, Fig. 4E); the first and second single crystalline semiconductor layers have substantially the same height from the surface of the semiconductor substrate (4, Fig. 4E); and the thickness of the semiconductor layer lower than a gate electrode of the MOS transistor is substantially the same thickness of the predetermined second single crystalline semiconductor layer (Fig. 4E).

Art Unit: 2824

Conclusion

The prior art made of record and not relied upon is considered pertinent to applicant's disclosure. The following US patents disclose relevant semiconductor structures pertaining to bipolar and CMOS combinations: 5100810, 6235567, 6365447 and 6555891.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Douglas M Menz whose telephone number is 571-272-1877. The examiner can normally be reached on M-F 8-5.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Richard Elms can be reached on 571-272-1869. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

DM

RICHARD ELMS
SUPERVISORY PATENT EXAMINER
TECHNOLOGY CENTER 2800